## **EUV Actinic Blank Inspection Tool Development**

#### **EUVL Symposium 2012**

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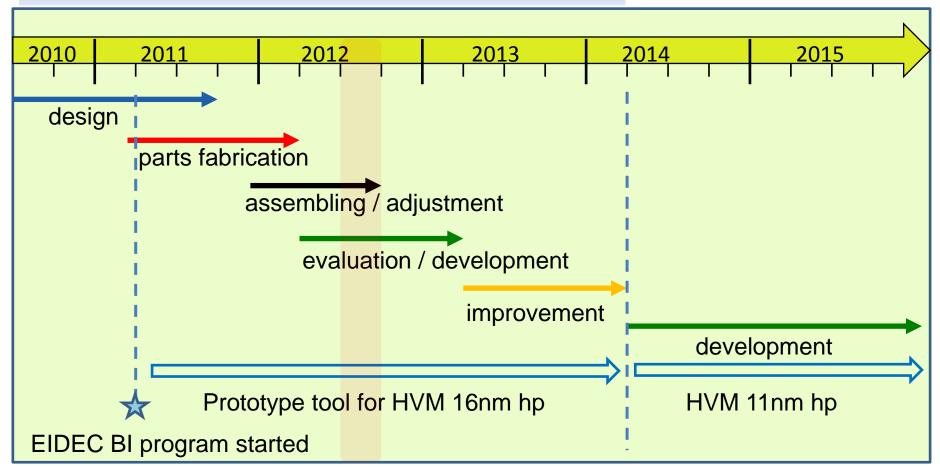
- 1. Introduction
- 2. Illumination efficiency improvement
- 3. Solutions to use a new EUV filter
- 4. High magnification review optics
- 5. Summary

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## ABI HVM Tool Development Schedule

#### EIDEC – Lasertec Blank Inspection Project

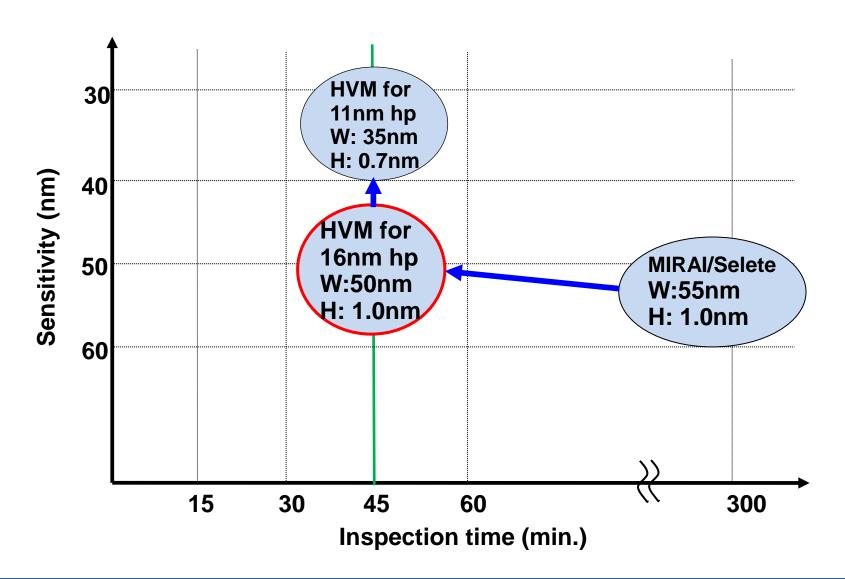


- -- Assembly of the ABI HVM tool has been completed.
- -- Adjustment and evaluation are in progress on schedule.

## **ABI HVM Tool**

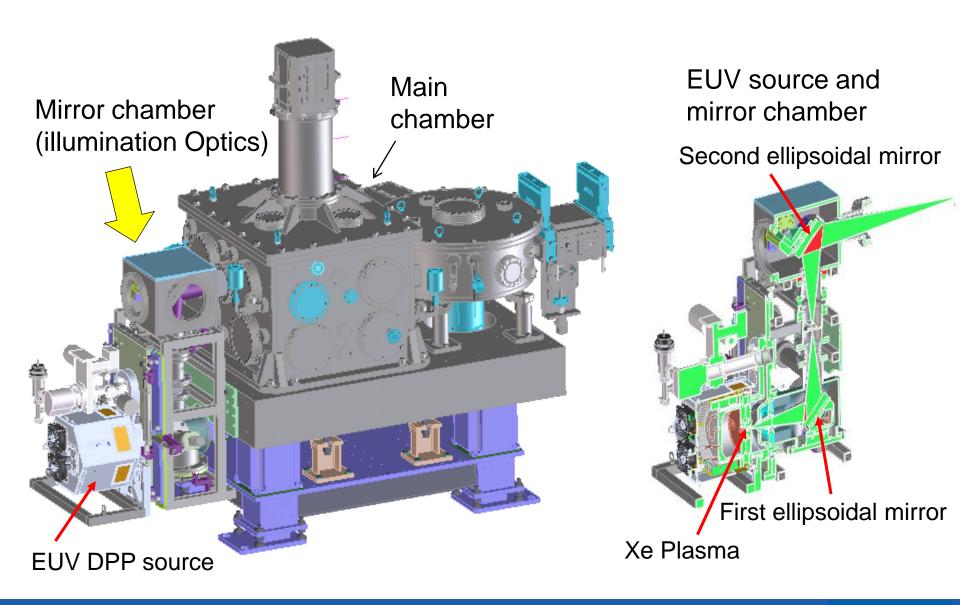


## Actinic mask blank inspection sensitivity roadmap



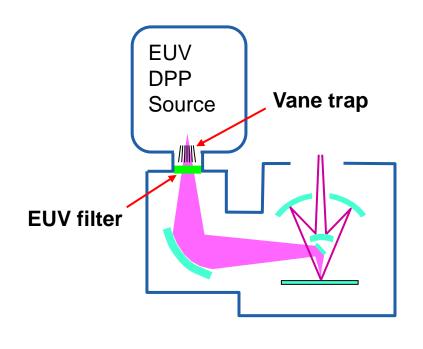
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## Illumination optics of the ABI tool

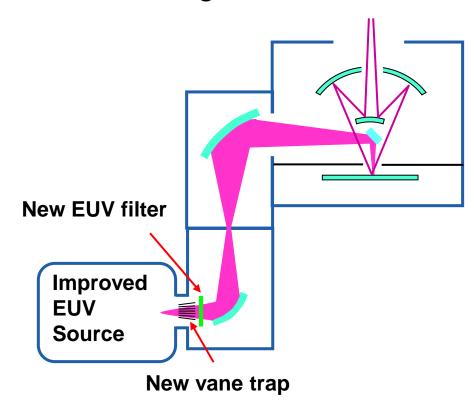


## Illumination optics for the HVM tool

#### 1. Previous design



#### 2. HVM design

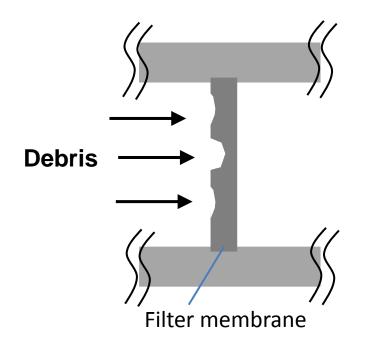


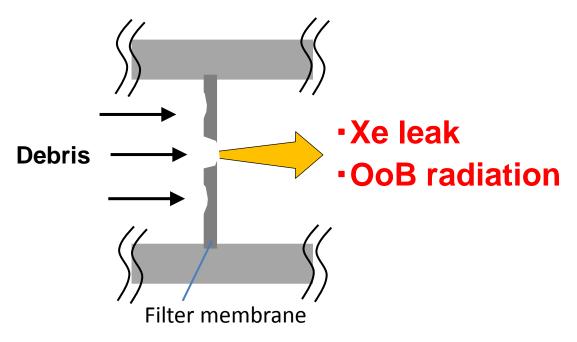
Two times higher transmission can be expected by improving the EUV filter and the vane trap

## Anticipated problems using a new EUV filter

Previous design

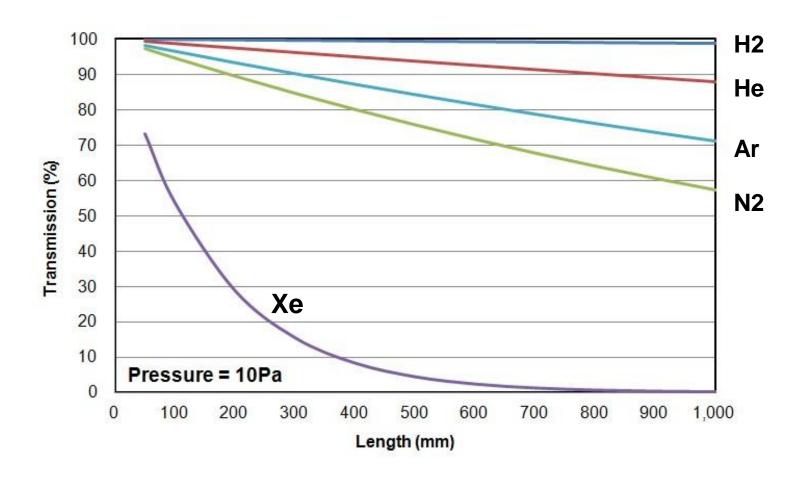
HVM design





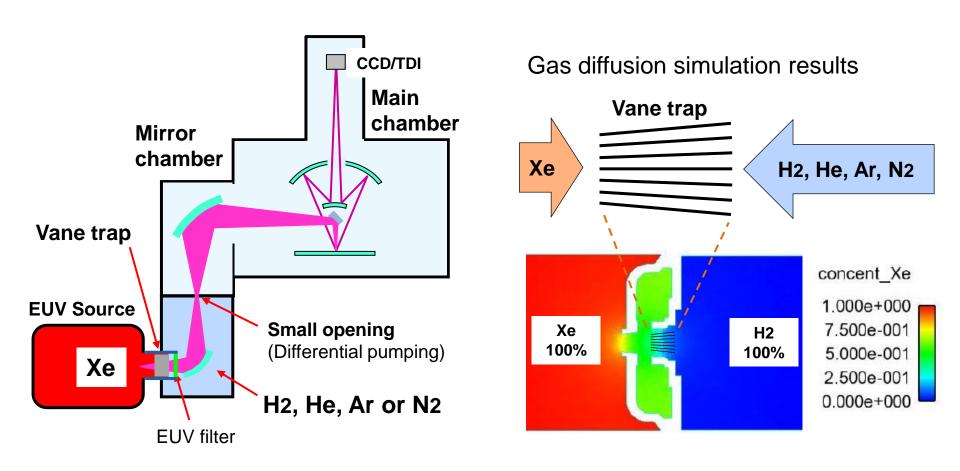
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#### Xe diffusion into the mirror chamber need to be suppressed



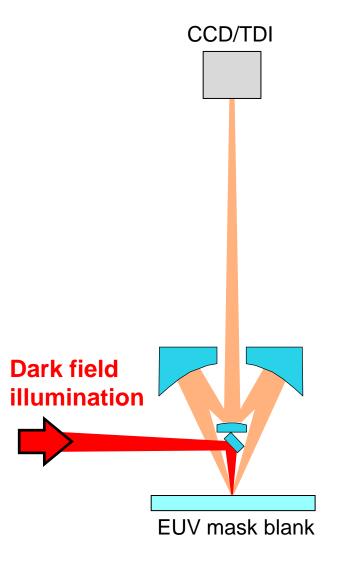
13.5nm radiation transmission in various gas

### Xe diffusion into the mirror chamber can be stopped

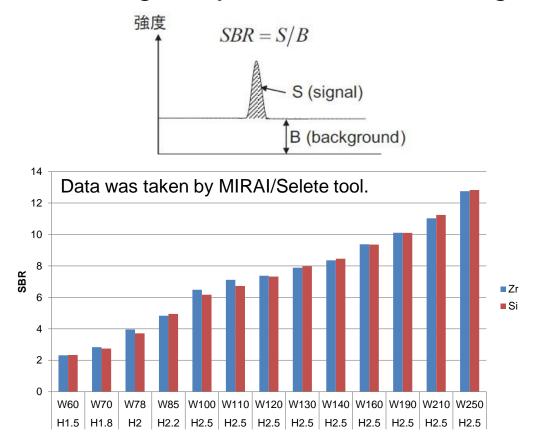


Xe diffusion can be stopped in the vane trap by transparent gas

## Out of band radiation does not affect sensitivity



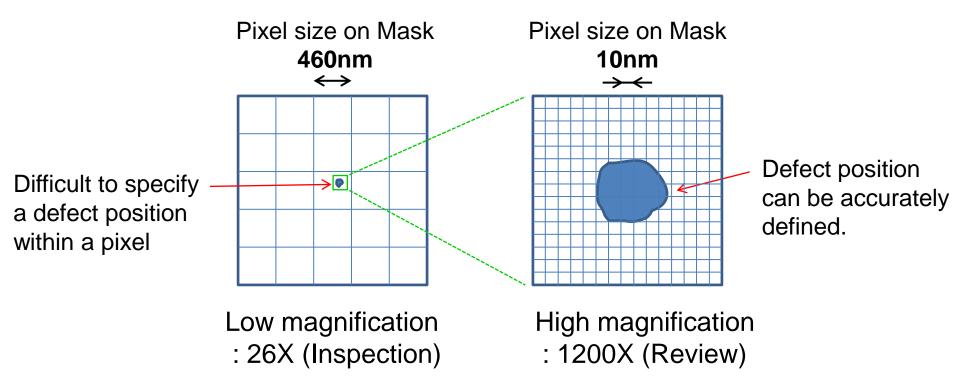
Sensitivity test using a Si filter which greatly transmits visible light.



Almost equal sensitivity was obtained between Zr and Si.

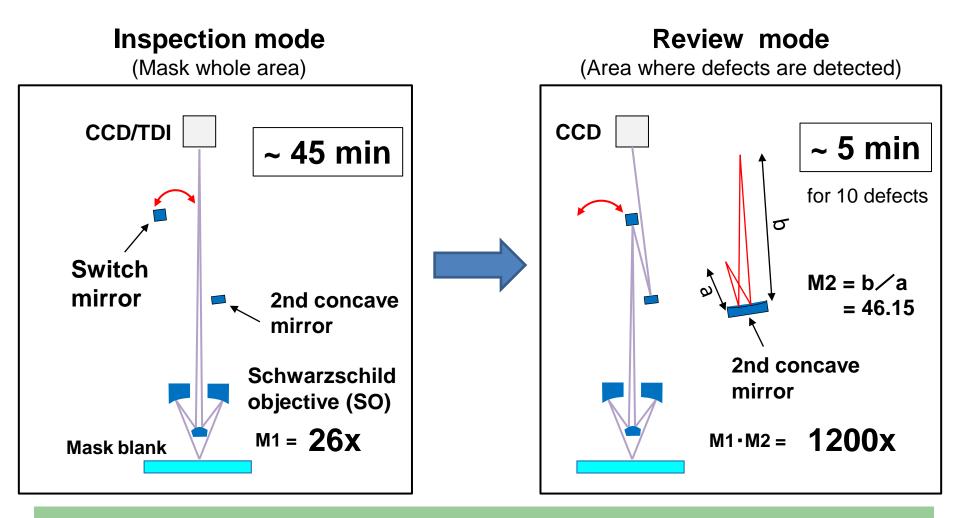
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## Purpose of the high magnification review optics



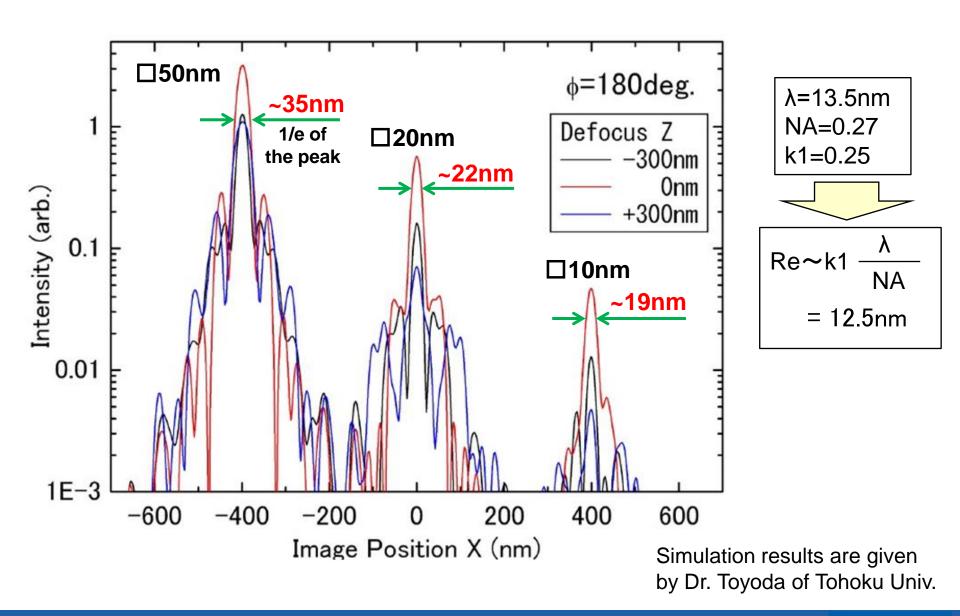
# 1200X magnification review mode: a basis for the accurate defect positioning

## Review mode integration



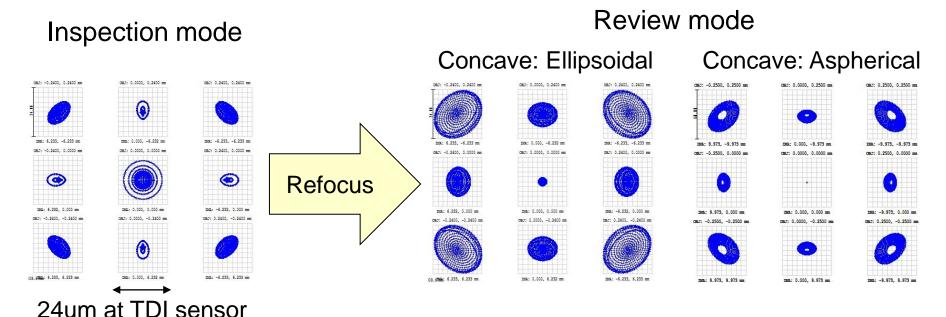
High-Speed Inspection & High Resolution Review implemented in one system

## Simulation results of the 1200X projection



#### Small aberration can be obtained at the center

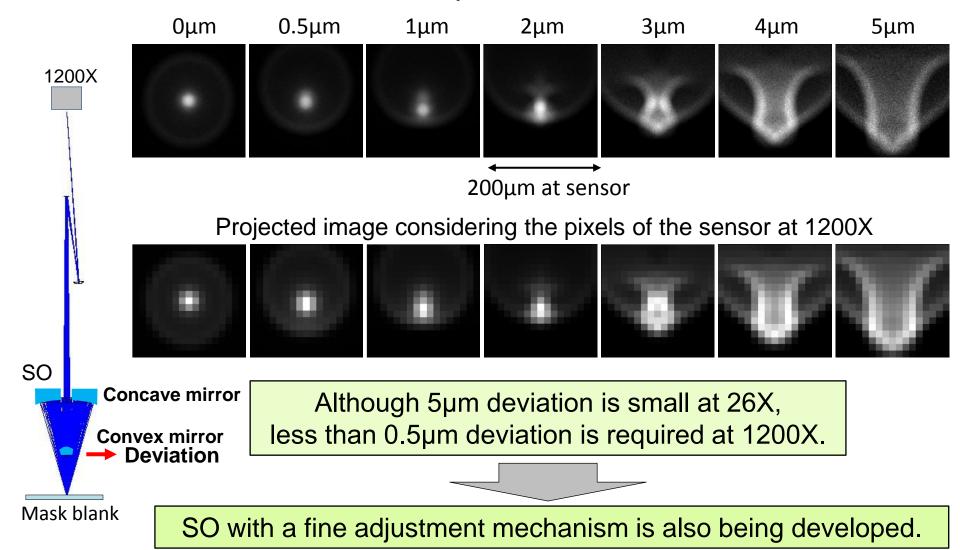
Spot diagrams in the 0.47x0.47mm area for the 26X SO



An improved SO using an aspherical concave mirror is also being developed.

## Review image degradation by the imperfection of SO

Deviation of the coaxiality of the convex and the concave mirror



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## Summary

- 1. ABI HVM tool has a target of < 45min inspection time by improving the illumination optics as well as EUV source.
- 2. In order to increase the illumination optics efficiency, a new EUV filter and a new vane trap are employed.
- 3. Xe diffusion can be suppressed by transparent gas.
  Also it has been demonstrated that the OoB radiation does not affect the inspection sensitivity.
- 4. 1200X magnification review optics are design based on the 26X SO. Also an improved SO is being developed.

# Acknowledgement

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- -- Prof. Kinoshita and Dr. Harada of Hyogo Univ.
- -- Dr. Toyoda of Tohoku Univ.

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